

(CS03-015)



Application No. 10/759,671

To: Commissioner of Patents
P.O. Box 1450
Alexandria, VA 22313-1450

From: George O. Saile, Reg. No. 119, 572
28 Davis Avenue
Poughkeepsie, NY 12603

Subject: Application No. 10/759, 671 16 January 2004

Poon et al.

DUAL STEP SOURCE/DRAIN EXTENSION JUNCTION ANNEAL TO REDUCE
THE JUNCTION DEPTH: MULTIPLE-PULSE LOW ENERGY LASER ANNEAL
COUPLED WITH RAPID THERMAL ANNEAL

Art Unit: 2812 Examiner: Walter L. Lindsay, Jr.

*enter per RCE
filed 327-06
PMG-19-06*

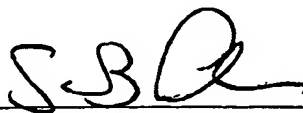
RESPONSE PATENT APPLICATION

Dear Sir:

In response to the Office Action dated August 9, 2005, please amend the above identified application for patent as follows:

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner of Patents, PO Box 1450, Alexandria, VA 22313-1450, on February 9, 2006.



Stephen B. Ackerman
Reg. No. 37, 761